2nd Announcement and Call for Papers

Photomask Japan 2019

April 16 (Tue.) - 18 (Thu.), 2019 PACIFICO Yokohama (Annex Hall), Yokohama, Japan

Symposium Chair: **Prof. Takeo Watanabe, University of Hyogo (Japan)**

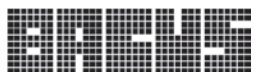
Organized by Photomask Japan and SPIE, Co-organized by BACUS and EMLC

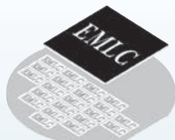
The 26th Symposium on Photomask and Next Generation Lithography Mask Technology

Abstract Due Date: November 30 (Fri.), 2018
＊Camera-Ready Abstract Submission is not required.
Manuscript Due Date: March 14 (Thu.), 2019
These are ***FIRM!***
Manuscripts are required of all accepted applicants and must be submitted in English.

Organized by

Co-organized by





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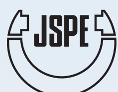

Papers are solicited on the following and related topics:

- **Materials for Photomasks**
- **Fabrication Process Steps and Equipment for Photomasks (Developing, Etching, Cleaning etc.)**
- **Photomask Writing Tools and Technologies including Multi-Beam EB Writer**
- **Tools and Technologies for Metrology/ Inspection/ Repair**
- **Technologies and Infrastructures for EUVL/ NIL/ FPD Masks**
- **Mask Data Preparations, EDA and DTCO**
- **Photomasks with RET: PSM, OPC, SMO and Multiple Patterning**
- **Photomask-related Lithography Technologies**
- **DSA (Directed Self-Assembly) related Mask Technologies**
- **Strategies and Business Challenges: Cost, Cycle-Time, ML2 etc.**
- **Mask/ Lithography related Technologies in Academia (Poster Session)**
- NEW **Patterning Technologies for Semiconductor and Electronic Devices**
- NEW **Semiconductor Manufacturing Technologies**
- NEW **EB Direct Writing, EB Lithography Technologies**

Tentative Program (The program is subject to change without notice.)

Technical Conferences

● April 16 (Tue.)	10:00 am to 6:00 pm
● April 17 (Wed.)	9:00 am to 8:00 pm
Poster Session	(4:00 pm to 6:00 pm)
Banquet	(6:00 pm to 8:00 pm)
● April 18 (Thu.)	9:00 am to 6:00 pm

Technical Exhibition

● April 16 (Tue.)	10:00 am to 5:00 pm
● April 17 (Wed.)	10:00 am to 5:00 pm

Banquet

● April 17 (Wed.)	6:00 pm to 8:00 pm

All abstracts are to be registered electronically via the PMJ website to get the qualification for abstract submission to the conference .

See the reverse page for more information ➔

For more information, contact:
Photomask Japan Secretariat
c/o JTB Communication Design, Inc.
Celestine Shiba Mitsui Bldg., 3-23-1 Shiba,
Minato-ku, Tokyo 105-8335, Japan
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E-mail: pmj@jtbcom.co.jp
http://www.photomask-japan.org

SPIE Proceedings Coordinator
E-mail: joels@spie.org

PMJ Website will begin accepting abstracts: October 4 (Thu.), 2018

＊Abstract Due Date: November 30 (Fri.), 2018

＊Manuscript Due Date: March 14 (Thu.), 2019

Camera-Ready Abstract Submission is not required in PMJ2019.

Abstracts will be published in Digest of Paper, which will be distributed to all participants at the symposium.

All abstracts must be registered electronically with the PMJ website at: **http://www.photomask-japan.org**

If electronic submission is not possible then authors are asked to contact the Photomask Japan Secretariat before the abstract due date.

All authors are strongly encouraged to submit their abstract by November 30, 2018.

Please note : the electronic abstract submission system will close on time and late abstracts will not be accepted.

And Manuscripts are required of all accepted applicants and must be submitted in English.

Please note: *This information is subject to change without notice. PMJ requests all prospective authors to regularly check the PMJ website for updates.*

To submit an abstract:

Abstracts must be written and presented **in English.**

All abstracts must be registered electronically **in a PDF file** via the conference website. For registration information, please visit the PMJ website.

Abstract Submission Information:

http://www.photomask-japan.org

All abstracts must contain the following information:

1. Title of Abstract:
Title should be in bold font using both upper and lower case.

2. Names of All Authors:
Names should be grouped by affiliation, listing Principal Author first. Please include both family and given names.

3. Abstract and Figures:
Text should be approximately 250 words, not exceeding one A4 page including figures.

4. Keywords:
List maximum of five keywords. Please choose at least one keyword for your abstract.

Your Abstract Reference Number will be automatically sent to you via e-mail as soon as your application has been received through the web page. If you do not receive a response within 24 hours, please contact the Abstract Submission Office.

Sample Abstract Format:

(1) Title

(2) Complete Author List

E.g., Akihiko Ando (Toshiba Memory Corporation, Japan),
Tsukasa Abe (Dai Nippon Printing Co., Ltd, Japan),
Yutaka Kodera (Toppan Printing Co., Ltd, Japan)

(3) Abstract Text

(4) Keyword(s)

(1) and (2) should be centered on the page.

(2) Authors names should be spelled out completely.

(3) should be 250 words.

Notification of Acceptance:

The Photomask Japan Program Committee will review all contributed abstracts. Applicants will be notified of acceptance or rejection by e-mail no later than the end of January 2019.

Mask / Lithography related Technology in Academia (Poster session)

PMJ offers an opportunity for university students or postdoctoral researchers to present their works on mask / lithography technology fields in a poster session. Those who wish to present their works are asked to submit an abstract in accordance with the PMJ call for papers.

Session Date: April 17, 2019（tentative）

Session Scope: Mask technology, lithography technology and applications

Object Presenter: Applicants should be university students or postdoctoral researchers

Registration Fee: Free for presenter

Abstract Submission Office:

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